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FIG. 1A

CRYSTALLIZATION STEP

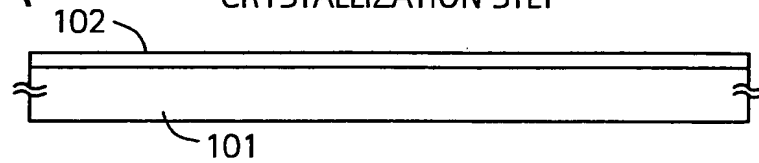


FIG. 1B

LASER IRRADIATION STEP

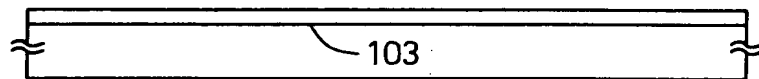


FIG. 1C

HEAT TREATMENT STEP IN REDUCING ATMOSPHERE

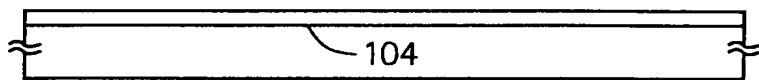


FIG. 1D

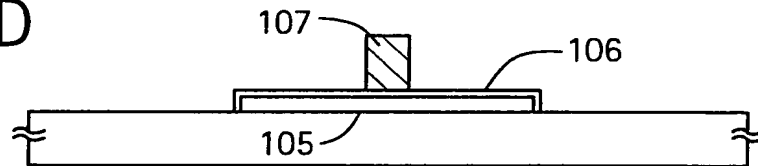


FIG. 1E

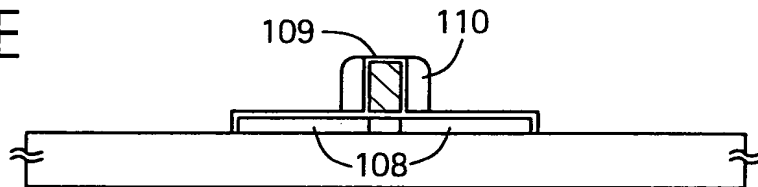


FIG. 1F

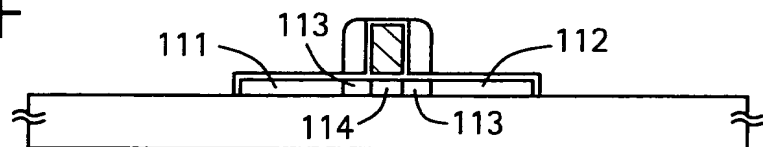


FIG. 1G

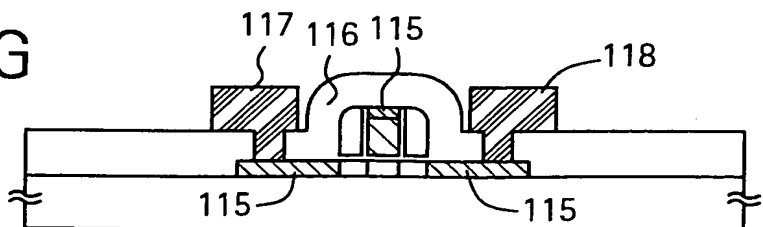


FIG. 2A

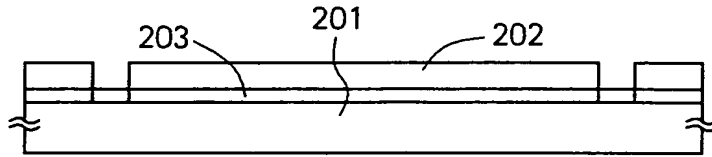


FIG. 2B

ADDING STEP OF PHOSPHORUS

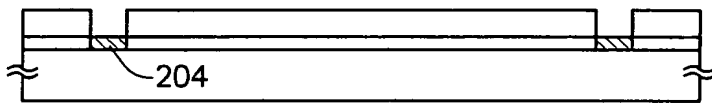


FIG. 2C

GETTERING STEP

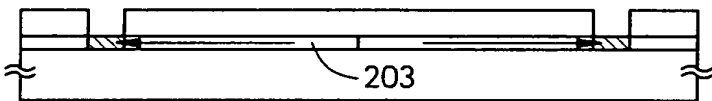


FIG. 2D

HEAT TREATMENT STEP IN REDUCING ATMOSPHERE

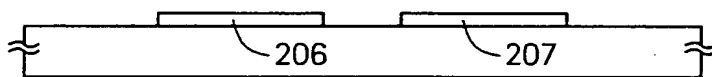


FIG. 3A

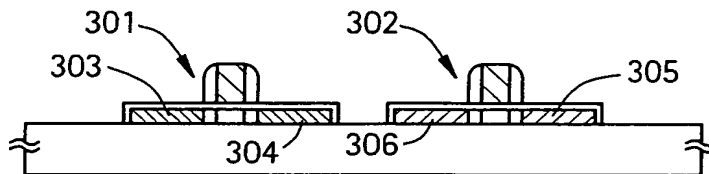


FIG. 3B

GETTERING STEP

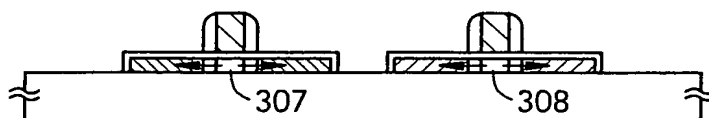


FIG. 4A

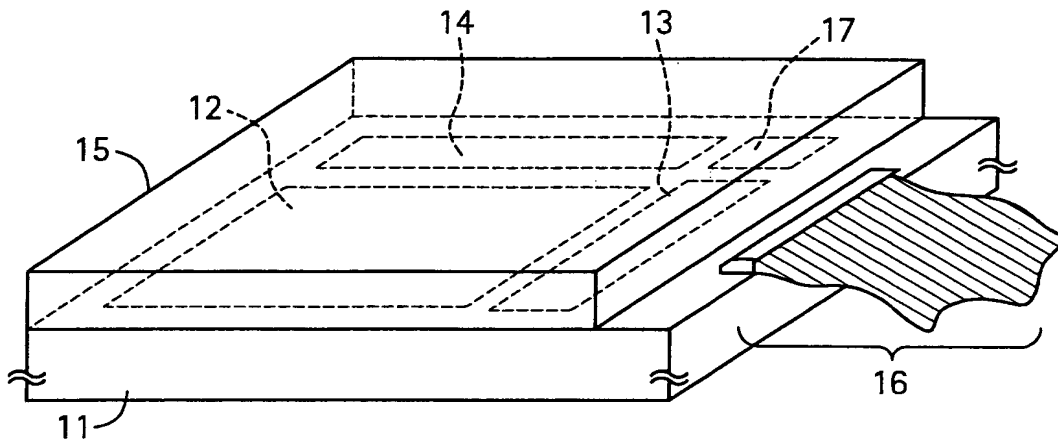


FIG. 4B

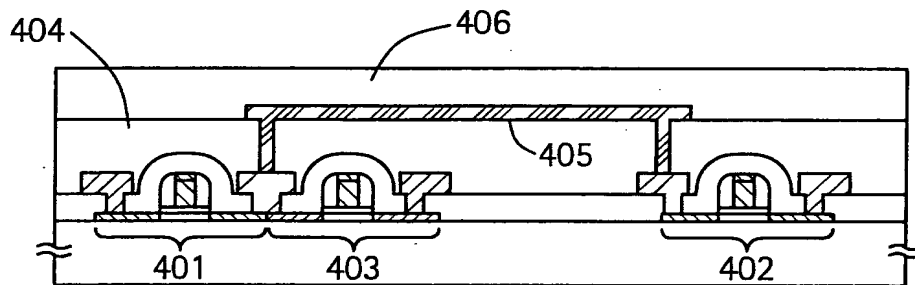


FIG. 4C

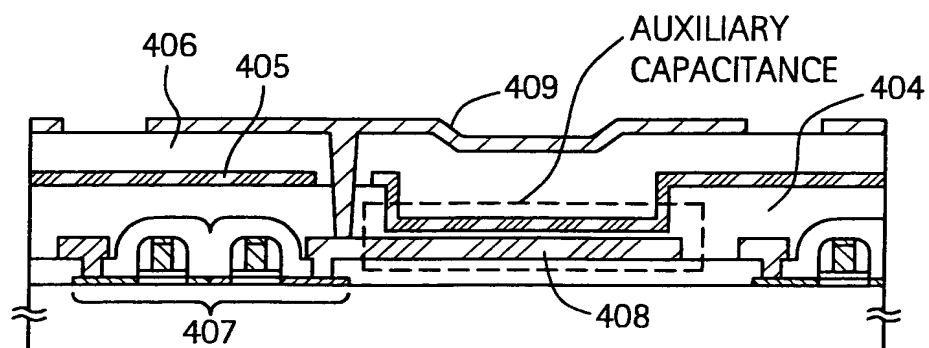


FIG. 5

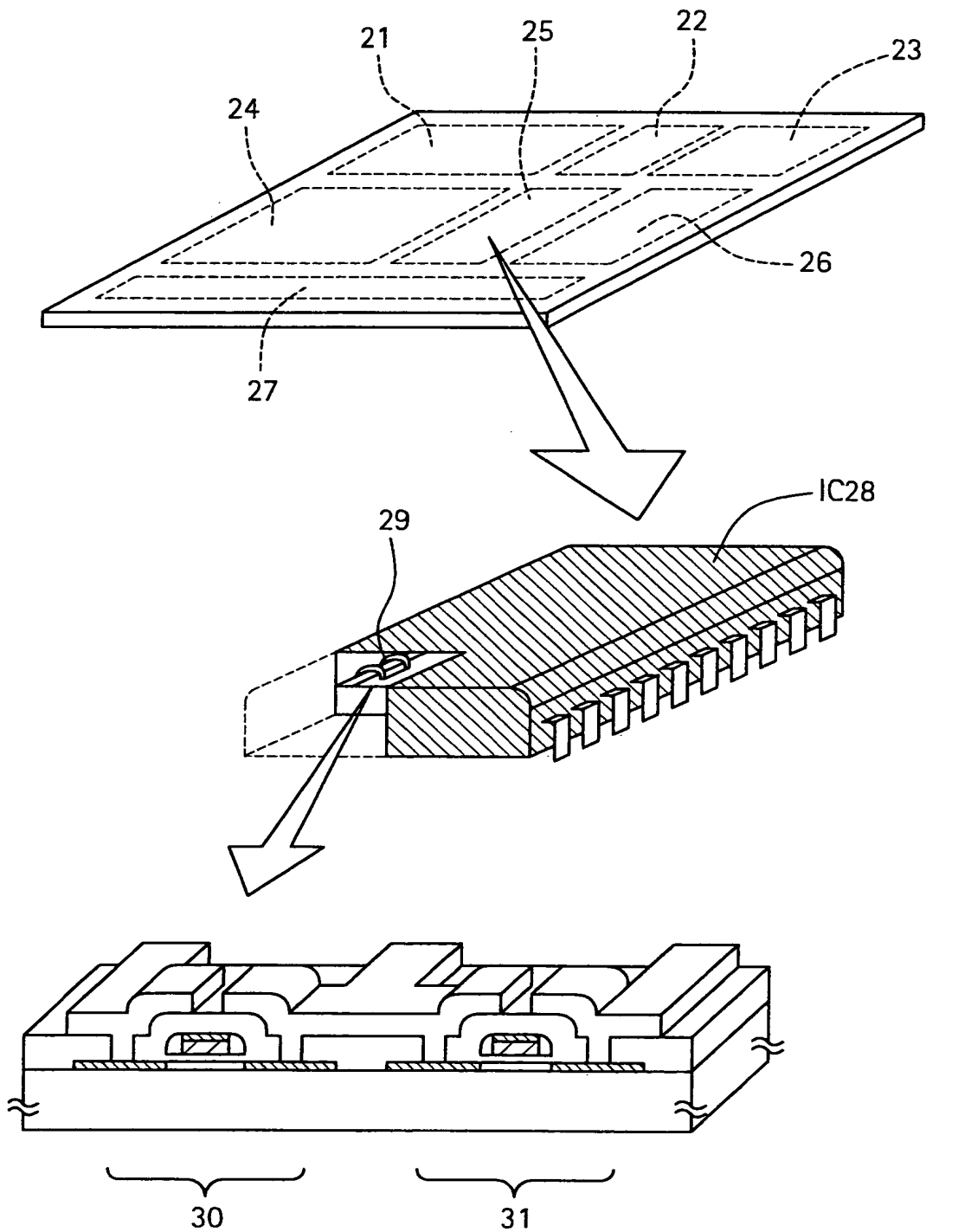


FIG. 6A

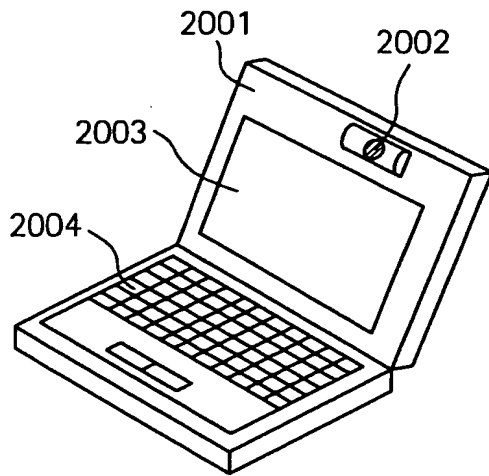


FIG. 6B

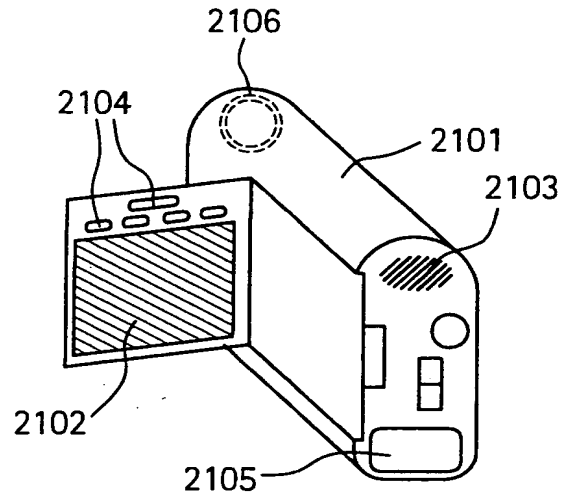


FIG. 6C

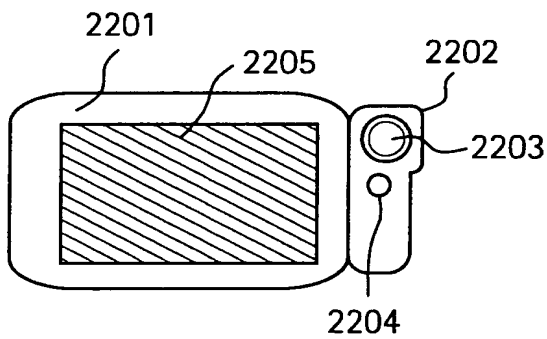


FIG. 6D

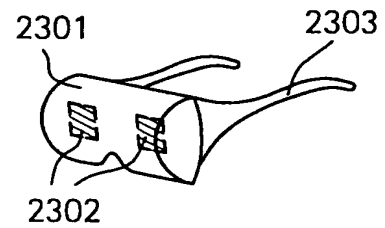


FIG. 6E

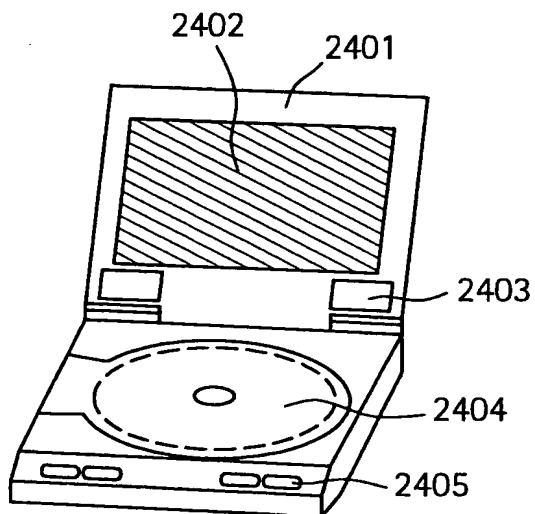


FIG. 6F

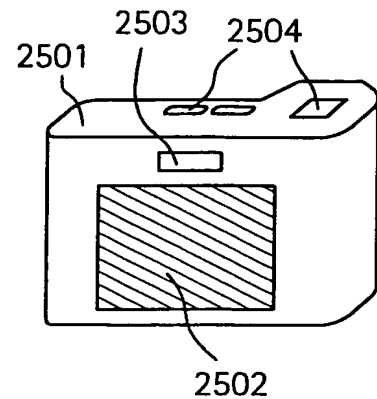


FIG. 7A

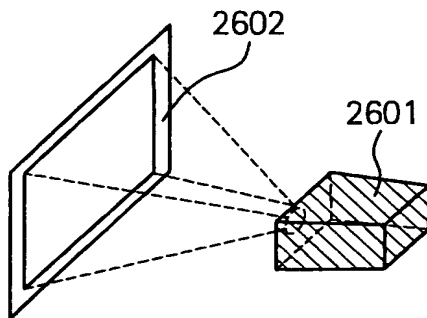


FIG. 7B

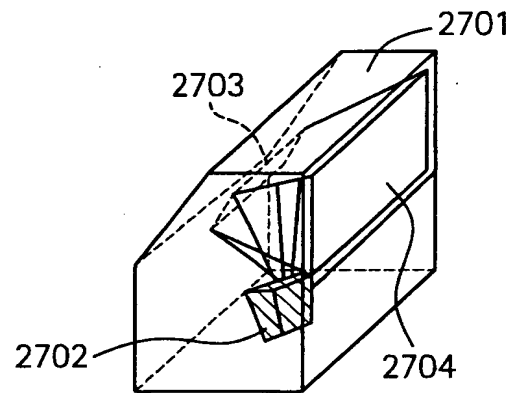


FIG. 7C

DISPLAY DEVICE (THREE-PLATE TYPE)

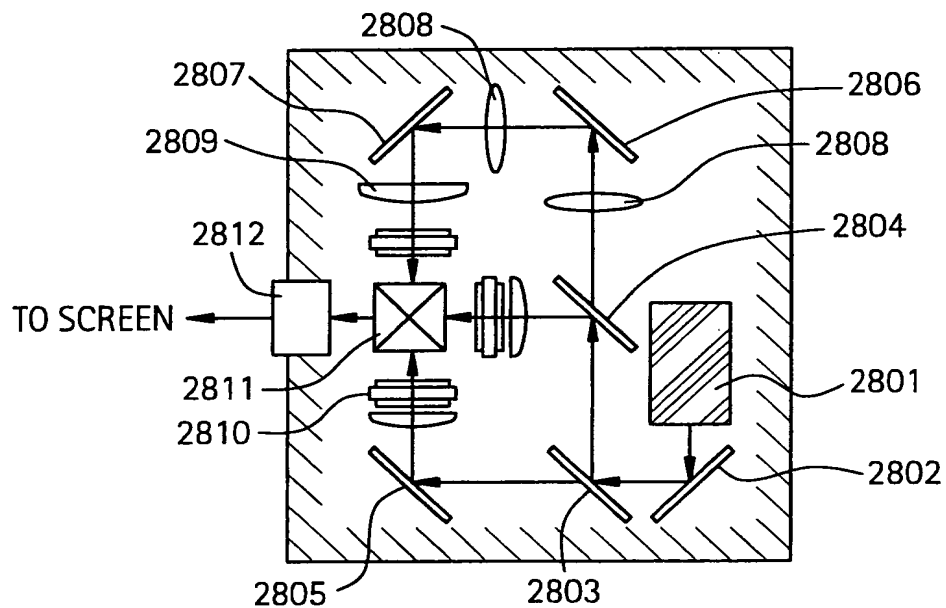


FIG. 7D

LIGHT SOURCE OPTICAL SYSTEM

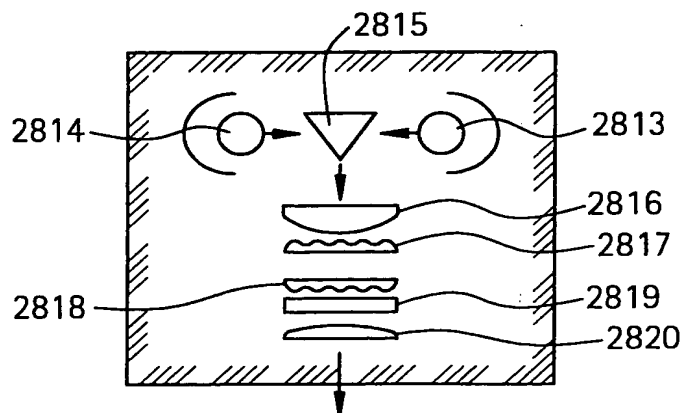


FIG. 8A

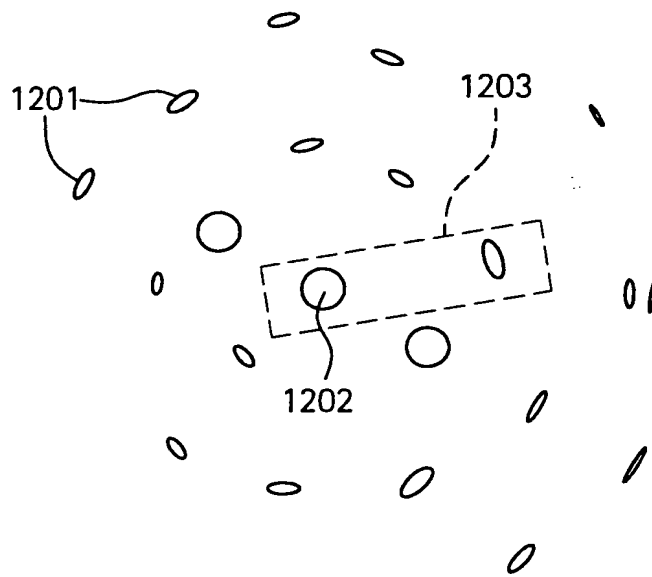


FIG. 8B

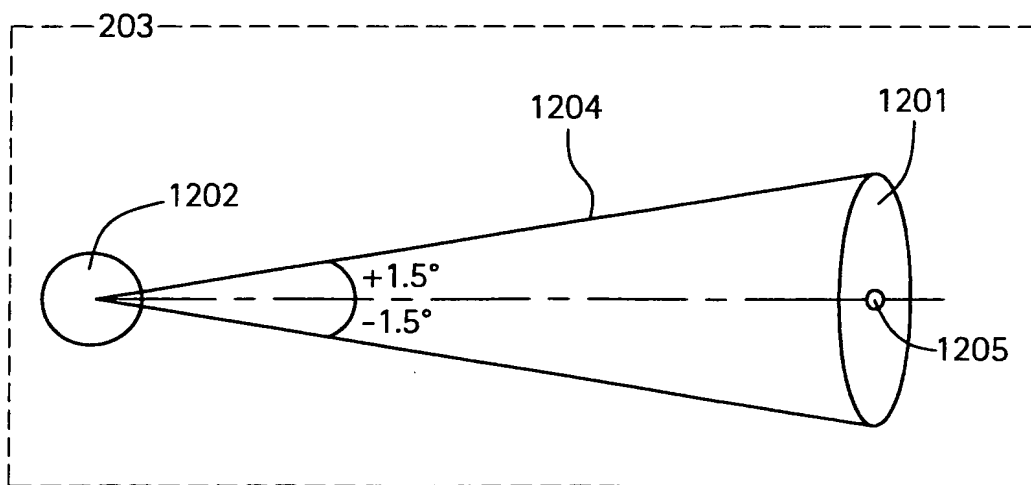


FIG. 9

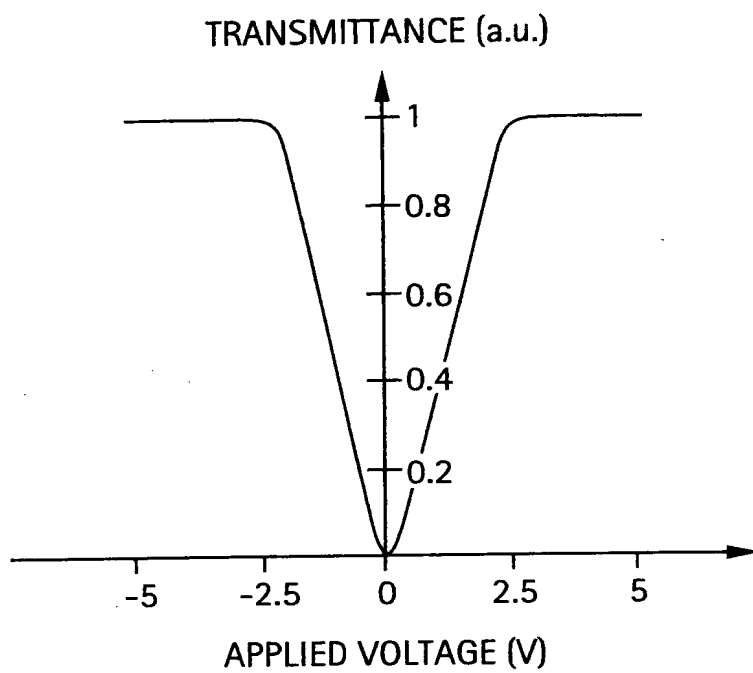


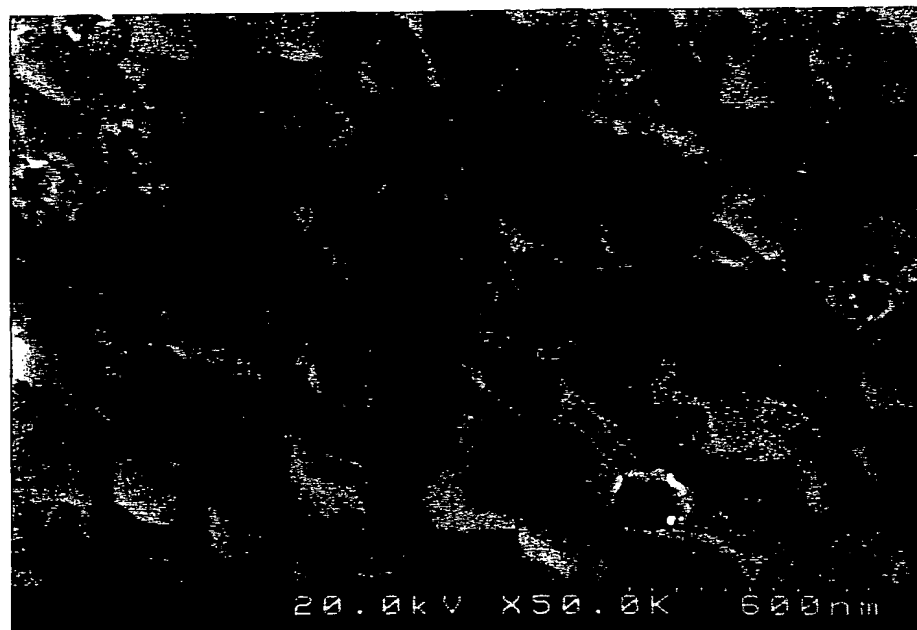
FIG. 10



BEFORE HIGH TEMPERATURE ANNEALING

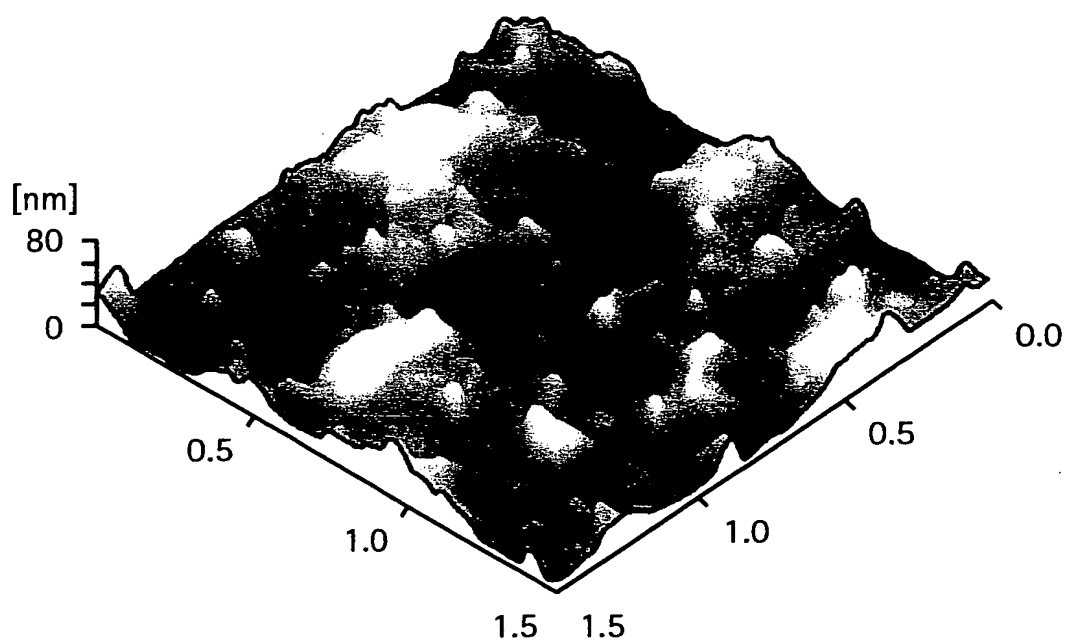
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FIG. 11



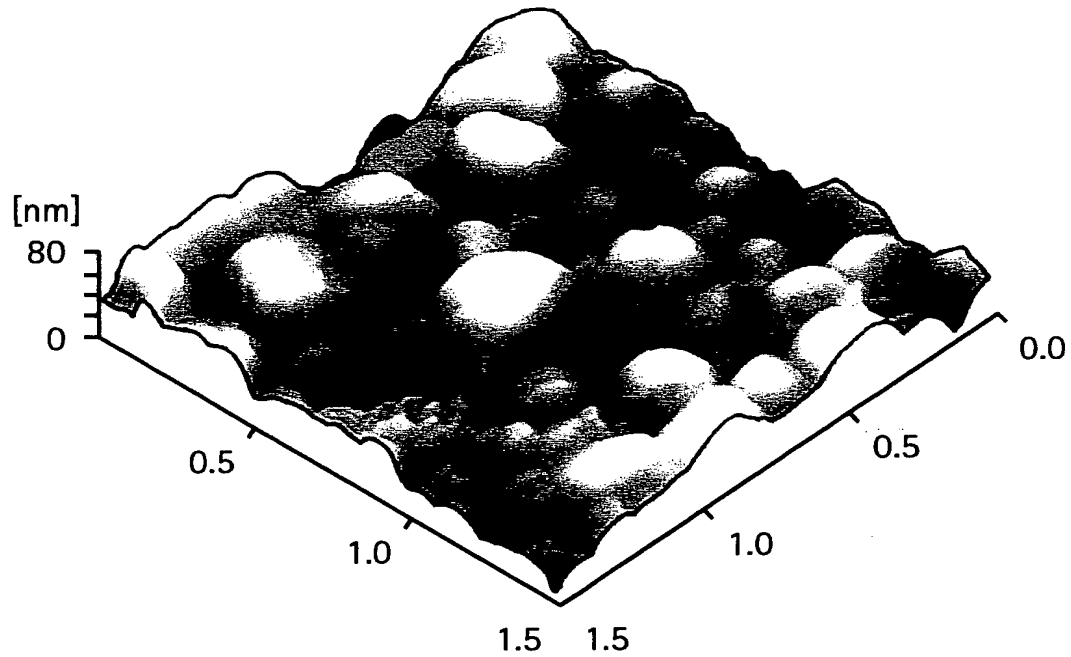
AFTER HIGH TEMPERATURE ANNEALING

FIG. 12



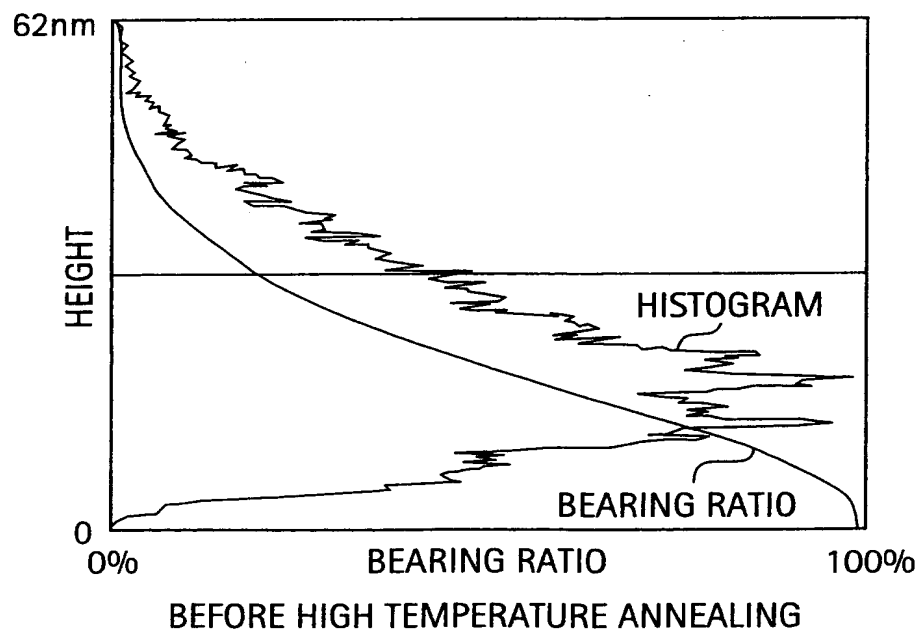
BEFORE HIGH TEMPERATURE ANNEALING

FIG. 13



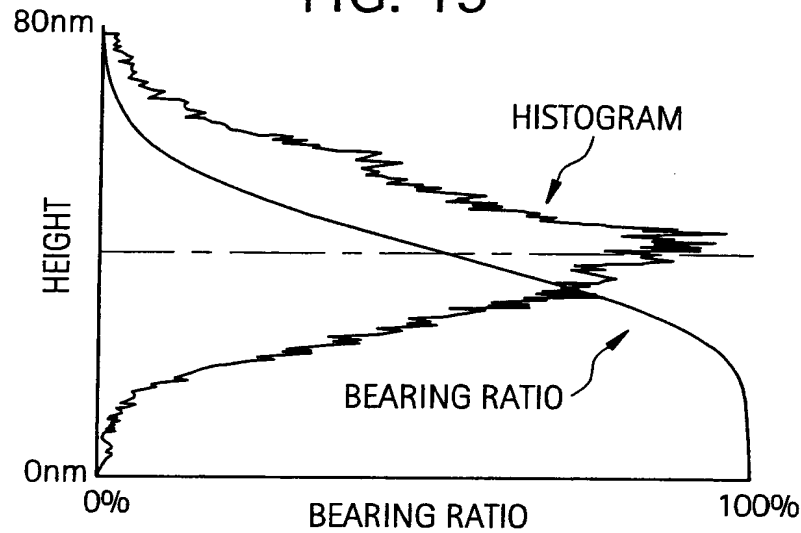
AFTER HIGH TEMPERATURE ANNEALING

FIG. 14



BEFORE HIGH TEMPERATURE ANNEALING

FIG. 15



AFTER HIGH TEMPERATURE ANNEALING

FIG. 16

OBSERVATION REGION	BEFORE HIGH TEMPERATURE ANNEALING	AFTER HIGH TEMPERATURE ANNEALING
1	13.623	40.925
2	20.027	51.126
3	20.629	59.364
4	21.798	48.539
5	16.666	55.341
6	15.097	46.510
7	13.120	57.655
8	14.035	51.120
9	12.599	54.416
10	20.699	36.945

MINIMUM VALUE (%)	12.60	36.95
MAXIMUM VALUE (%)	21.80	59.36
AVERAGE VALUE (%)	16.83	50.19
STANDARD DEVIATION τ	3.61	7.18

BEARING RATIO AT 2^{-1} (P-V VALUE) (%)